

Paragraph beginning at page 5, line 1 has been amended as follows:

A2  
The work function of the material of the third layer is preferably greater than 4.0 eV. The higher work function material is suitably a metal or an oxide. The higher work function material and/or the third layer itself preferably has an electrical conductivity greater than  $10^5 (\Omega \cdot \text{cm})^{-1}$ . The higher work function material is preferably Al, Cu, Ag, Au or Pt; or an alloy of two or more of those metals; or an alloy of one or more of those metals together with another metal; or an oxide such as tin oxide or indium-tin oxide (ITO). The thickness of the third layer is preferably in the range from 1000 Å to 10000 Å, preferably in the range from 2000 Å to 6000 Å, and most preferably around 4000 Å.

Please insert a new paragraph beginning at page 7, following line 5 as follows:

A3  
--figure 1 shows a typical cross-sectional structure of a prior art organic light-emissive device;

Paragraph beginning at page 7, line 28 has been amended as follows:

A4  
To form the device of figure 2 a transparent layer of ITO to form the anode electrode 10 may first be deposited on a sheet of glass 14. The glass sheet could be a sheet of sodalime or borosilicate glass of a thickness of, for instance, 1mm. The thickness of the ITO coating is suitably around 100 to 150nm and the ITO suitably has a resistance of between 10 and 30  $\Omega/\square$ . ITO-coated glass substrates of this type are commercially available. As an alternative to glass, the sheet 14 could be formed of perspex. As an alternative to ITO, gold or TO could be used as the anode.